We claim:

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1	1	А	resonator	device	comprising:
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- a first piezoelectric resonator and a second piezoelectric resonator, wherein the
- 3 first piezoelectric resonator and the second piezoelectric resonator each have a
- 4 piezoelectric layer having a first surface and a second surface, a first electrode on the
- 5 first surface and a second electrode on the second surface; and
- a detuning layer sequence arranged on the first piezoelectric resonator
- 7 wherein
- 8 the detuning layer sequence is arranged on the first electrode of the first
- 9 piezoelectric resonator or on the second electrode of the first piezoelectric resonator;
- 10 and
- the detuning layer sequence comprises at least a first layer having a first
- 12 acoustic impedance and a second layer having a second acoustic impedance in order to
- shift a resonance frequency of the first piezoelectric resonator relative to the resonance
- 14 frequency of the second piezoelectric resonator, wherein the first acoustic impedance
- is lower than the second acoustic impedance.
- 1 2. The resonator device according to claim 1, wherein the acoustic impedances of
- 2 the layers of the detuning layer sequence differ from each other by the factor 2.

- 1 3. The resonator device according to claim 1, wherein the impedance of the layer
- 2 having a high acoustic impedance is between $60 \times 10^6 \frac{kg}{s \cdot m^2}$ and $100 \times 10^6 \frac{kg}{s \cdot m^2}$, and
- 3 wherein the impedance of a layer having a low acoustic impedance is between 10x10⁶
- $4 \qquad \frac{kg}{s \cdot m^2} \text{ and } 30 \times 10^6 \frac{kg}{s \cdot m^2}.$
- 1 4. The resonator device according to claim 1, wherein the layer having a low
- 2 acoustic impedance comprises Al or SiO₂.
- 1 5. The resonator device according to claim 1, wherein the layer having a high
- 2 acoustic impedance comprises W, Mo, Pt or Ta₂O₅.
- 1 6. The resonator device according to claim 1, wherein the first layer having a low
- 2 acoustic impedance has a thickness in the range of 50 nm to 200 nm, and wherein the
- 3 second layer having a high acoustic impedance has a thickness in the range of 10 nm
- 4 to 60 nm.
- 1 7. The resonator device according to claim 1, having a substrate, on which the
- 2 first and the second piezoelectric resonator are arranged in an acoustically isolated
- 3 way.
- 1 8. The resonator device according to claim 7, wherein a cavity or an acoustic
- 2 reflector is arranged between the first piezoelectric resonator and the substrate and
- 3 between the second piezoelectric resonator and the substrate for acoustic isolation.

- 1 9. The resonator device according to claim 1, wherein the resonance frequencies
- 2 of the piezoelectric resonator and of the second piezoelectric resonator differ by 2% to
- 3 3%.
- 1 10. The resonator device according to claim 1, wherein the second piezoelectric
- 2 resonator is connected between a first node and a second node, and wherein the first
- 3 piezoelectric resonator is connected between the second node and a reference
- 4 potential.
- 1 11. The resonator device according to claim 1, wherein the first and the second
- 2 piezoelectric resonator include a plurality of piezoelectric layers.

1	12. A filter comprising a resonator device, the resonator device comprising:
2	a first piezoelectric resonator and a second piezoelectric resonator, wherein the
3	first piezoelectric resonator and the second piezoelectric resonator each have a
4	piezoelectric layer having a first surface and a second surface, a first electrode on the
5	first surface and a second electrode on the second surface; and
6	a detuning layer sequence arranged on the first piezoelectric resonator
7	wherein
8	the detuning layer sequence is arranged on the first electrode of the first
9	piezoelectric resonator or on the second electrode of the first piezoelectric resonator;
10	and
11	the detuning layer sequence comprises at least a first layer having a first
12	acoustic impedance and a second layer having a second acoustic impedance in order to
13	shift a resonance frequency of the first piezoelectric resonator relative to the resonance
14	frequency of the second piezoelectric resonator, wherein the first acoustic impedance

is lower than the second acoustic impedance.

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- 1 13. A resonator device comprising:
- 2 a piezoelectric layer having a first and a second surface,
- a first electrode arranged on the first surface and a second electrode arranged
- 4 on the second surface opposite of the first electrode;
- 5 a third electrode arranged on the first surface and a fourth electrode arranged
- 6 on the second surface opposite of the third electrode; and
- a detuning layer sequence arranged on the first electrode or on the second
- 8 electrode; and
- 9 the detuning layer sequence comprises at least a first layer having a first
- 10 acoustic impedance and a second layer having a second acoustic impedance, wherein
- the first acoustic impedance is lower than the second acoustic impedance.
- 1 14. The resonator device according to claim 13, wherein the acoustic impedances
- 2 of the layers of the detuning layer sequence differ from each other by the factor 2.
- 1 15. The resonator device according to claim 13, wherein the impedance of the
- 2 layer having a high acoustic impedance is between $60x10^6 \frac{kg}{s \cdot m^2}$ and $100x10^6 \frac{kg}{s \cdot m^2}$,
- 3 and wherein the impedance of a layer having a low acoustic impedance is between
- 4 $10 \times 10^6 \frac{kg}{s \cdot m^2}$ and $30 \times 10^6 \frac{kg}{s \cdot m^2}$.
- 1 16. The resonator device according to claim 13, wherein the layer having a low
- 2 acoustic impedance comprises Al or SiO₂.

- 1 17. The resonator device according to claim 13, wherein the layer having a high.
- 2 acoustic impedance comprises W, Mo, Pt or Ta₂O₅.
- 1 18. The resonator device according to claim 13, wherein the first layer having a
- 2 low acoustic impedance has a thickness in the range of 50 nm to 200 nm, and wherein
- 3 the second layer having a high acoustic impedance has a thickness in the range of 10
- 4 nm to 60 nm.
- 1 19. The resonator device according to claim 13, having a substrate, on which the
- 2 piezoelectric layer is arranged in an acoustically isolated way.
- 1 20. The resonator device according to claim 19, wherein a cavity or an acoustic
- 2 reflector is arranged between the piezoelectric layer and the substrate for acoustic
- 3 isolation.
- 1 21. The resonator device according to claim 13, wherein the resonance frequencies
- 2 of the resonator device differ by 2% to 3%.
- 1 22. The resonator device according to claim 13, wherein the third and fourth
- 2 electrodes are connected between a first node and a second node, and wherein the first
- 3 and second electrodes are connected between the second node and a reference
- 4 potential.
- 1 23. The resonator device according to claim 13, wherein the piezoelectric layer
- 2 includes a plurality of piezoelectric layers.